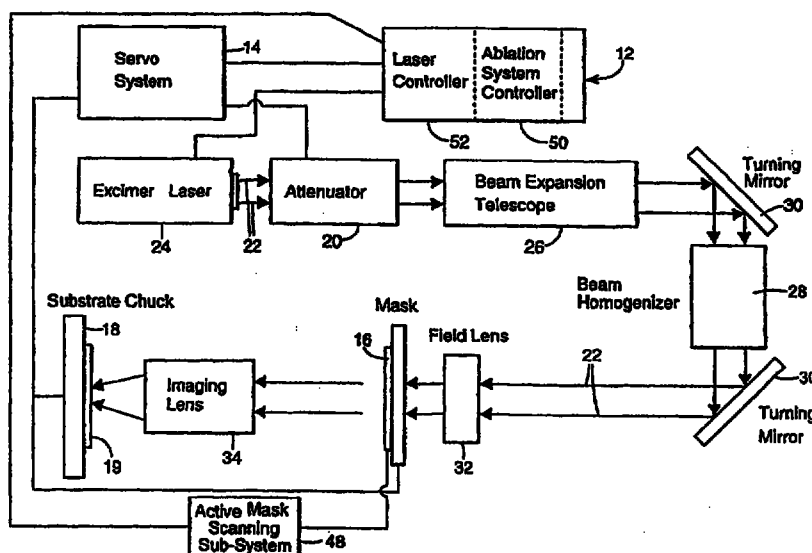




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(54) Title: MASK ORBITING FOR LASER ABLATED FEATURE FORMATION**(57) Abstract**

This invention concerns a process useful for ablating features from a substrate, including the steps of illuminating the substrate with laser light that has passed through a mask to form an ablated feature in the substrate, wherein the mask is orbited perpendicular to the angle of the laser light during formation of the feature thereby forming a selected wall shape. This invention also concerns an apparatus useful for making holes in a substrate having a radiation source; a mask positioned between the radiation source and a substrate to be irradiated with radiation from the radiation source, wherein the mask is capable of following a trajectory perpendicular to the angle of the radiation.